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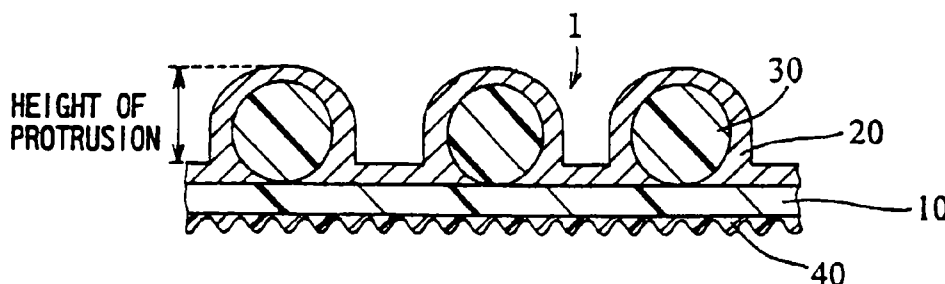
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ning of each regular issue of the PCT Gazette.

(54) Title: REFLECTOR, SIDELIGHT TYPE BACKLIGHTING APPARATUS AND REFLECTOR SUBSTRATE



(57) Abstract: An object of the invention is to provide a sidelight type backlighting apparatus having high brightness, which is yet reduced in uneven brightness, and to provide a reflector substrate having a surface profile necessary for obtaining such apparatus and a reflector having high brightness and long durability in which the reflector substrate is implemented. A buffer against strain is formed by providing space by protrusions or the like between a light guiding plate of a planar light source apparatus and a reflecting surface of a reflection sheet provided on one main surface of the light guiding plate. Further, a base layer, a metallic layer mainly containing silver, and a light transmitting oxide layer are laminated on the substrate in this order to form a reflection layer.

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